Number	Hits	Search Text	DB	Time stamp
1	11872	(resistance or resistivity) with silicide	USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:30
2	1131	((resistance or resistivity) with silicide) with electric\$4	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:31
3	705978	electrical adj resistivity of silicide	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:31
4	94	electrical adj resistivity with silicide	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:51
5	4	(aluminum adj silicide) same tantalum same (resistivity or resistance)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/01 15:36
6	11	<pre>(aluminum adj silicide) with (resistivity or resistance)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/01 15:39
7	4600	tantalum with (resistivity or resistance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/01 15:37
8	260	(tantalum with (resistivity or resistance)) with electrical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/01 15:37
9	494	aluminum with silicide with (resistivity or resistance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/01 15:39
10	52	(aluminum with silicide with (resistivity or resistance)) with electric\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/01 15:39
11	611	electrical adj resistivity with silicon	USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:51
12	41	electrical adj resistivity adj silicon	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:52
_	2	6303415.pn.	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/06/01 15:29
_	2052	tft and crystalliz\$5 and gate and source and drain	DERWENT USPAT; US-PGPUB; EPO; JPO;	2002/12/04 16:12
_	704	(tft and crystalliz\$5 and gate and source and drain) and cataly\$3	DERWENT USPAT; US-PGPUB; EPO; JPO;	2002/12/04 14:40
_	576	((tft and crystalliz\$5 and gate and source and drain) and cataly\$3) and (active adj layer)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2002/12/04 14:41
-	270	(((tft and crystalliz\$5 and gate and source and drain) and cataly\$3) and (active adj layer)) and getter\$3	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 14:46

-	212		USPAT;	2002/12/04
		source and drain) and cataly\$3) and	US-PGPUB;	14:48
		(active adj layer)) and getter\$3) and	EPO; JPO;	
		tantalum and nickel	DERWENT	
-	5	((((tft and crystalliz\$5 and gate and	USPAT;	2002/12/04
-		source and drain) and cataly\$3) and	US-PGPUB;	16:13
		(active adj layer)) and getter\$3) and	EPO; JPO;	
		tantalum and nickel) and @ad<19970610	DERWENT	
-	303	(crystalliz\$5 same silicon same cataly\$3)	USPAT;	2002/12/04
ļ		and getter\$3	US-PGPUB;	16:13
			EPO; JPO;	
İ			DERWENT	
-	24		USPAT;	2002/12/06
		cataly\$3) and getter\$3) and @ad<19970610	US-PGPUB;	11:32
			EPO; JPO;	
			DERWENT	
-	2	5550070.pn.	USPAT;	2002/12/04
		,	US-PGPUB;	17:10
			EPO; JPO;	
			DERWENT	
-	6		USPAT	2002/12/04
	["5330935" "5403772" "5426064").PN.		17:45
-	44	5550070.URPN.	USPAT	2002/12/04
				18:06
-	168	phosphorus same nickel same getter\$3	USPAT;	2002/12/06
			US-PGPUB;	11:31
	1		EPO; JPO;	
			DERWENT	
-	19	(phosphorus same nickel same getter\$3)	USPAT;	2002/12/06
1		and @ad<19970610	US-PGPUB;	12:01
ŀ			EPO; JPO;	
			DERWENT	1 ((
-	2005	gate with tantalum	USPAT;	2002/12/06
			US-PGPUB;	12:00
	ŀ		EPO; JPO;	
			DERWENT	
-	840	(gate with tantalum) and @ad<19970610	USPAT;	2002/12/06
			US-PGPUB;	13:45
			EPO; JPO;	
			DERWENT	2002/12/06
-	31	((gate with tantalum) and @ad<19970610)	USPAT;	2002/12/06
		and crystalliz\$5 and cataly\$3	US-PGPUB;	13:35
			EPO; JPO; DERWENT	
	140	(2002/12/06
-	148	(nickel or ni) with (source or drain)	USPAT;	1
	1	with channel	US-PGPUB; EPO; JPO;	14:48
			DERWENT	
1_	20	((nickel or ni) with (source or drain)	USPAT;	2002/12/06
-	20	with channel) with concentration	US-PGPUB;	13:37
		with channel, with concentration	EPO; JPO;	13.37
	1		DERWENT	
_	74	((nickel or ni) with (source or drain)	USPAT;	2002/12/06
_	'4	with channel) and @ad<19970610	US-PGPUB;	14:15
	[with diamer, and gad(19970010	EPO; JPO;	
			DERWENT	
l _	149	cataly\$3 with channel with less	USPAT;	2002/12/06
		occurity arou ordinater arou resp	EPO; JPO;	14:21
			DERWENT	
-	109	(cataly\$3 with channel with less) and	USPAT;	2002/12/06
		@ad<19970610	US-PGPUB;	14:16
	[EPO; JPO;	
	[DERWENT	
-	47	((cataly\$3 with channel with less) and	USPAT;	2002/12/06
]	@ad<19970610) and (nickel or ni)	US-PGPUB;	14:16
1	[EPO; JPO;	
	[DERWENT	
_	0	(cataly\$3 with channel with less) and	USPAT;	2002/12/06
	1	"5.times.10.sup.16."	EPO; JPO;	14:21
		<u>-</u>	DERWENT	1

_	3	(ni or nickel) with channel with	USPAT;	2002/12/06
		"5.times.10.sup.16"	EPO; JPO;	14:23
		_	DERWENT	
_	1 0	(ni or fe or co or pd or pt or cu or au)	USPAT;	2002/12/06
		with channel with "5.times.10.sup.16"	EPO; JPO;	14:25
			DERWENT	
_	3	(nickel or iron or gold or copper or	USPAT;	2002/12/06
		platinum or palladium or cobalt) with	EPO; JPO;	14:26
		channel with "5.times.10.sup.16"	DERWENT	117.20
				2002/12/06
-	0	(nickel or iron or gold or copper or	USPAT;	1
		platinum or palladium or cobalt) with	EPO; JPO;	14:26
		channel with "5.times.10.sup.15"	DERWENT	
-	0	(nickel or iron or gold or copper or	USPAT;	2002/12/06
		platinum or palladium or cobalt) with	EPO; JPO;	14:26
		channel with "5.times.10.sup.14"	DERWENT	
-	1	(nickel or iron or gold or copper or	USPAT;	2002/12/06
		platinum or palladium or cobalt) with	EPO; JPO;	14:26
		channel with "5.times.10.sup.17"	DERWENT	
_	5	(nickel or iron or gold or copper or	USPAT;	2002/12/06
	1	platinum or palladium or cobalt) with	EPO; JPO;	14:31
		channel with "1.times.10.sup.16"	DERWENT	
1_	0	(nickel or iron or gold or copper or	USPAT;	2002/12/06
	1		EPO; JPO;	14:45
	Ì	platinum or palladium or cobalt) with		+ 3 • 3 >
		channel with "1.times.10.sup.15"	DERWENT	2002/12/06
-	2	6303415.pn.	USPAT;	2002/12/06
			EPO; JPO;	14:45
			DERWENT	
-	77	(nickel or ni) same (source or drain)	USPAT;	2002/12/06
		same channel same order\$1	US-PGPUB;	14:51
			EPO; JPO;	
			DERWENT	
_	16	((nickel or ni) same (source or drain)	USPAT;	2002/12/06
j		same channel same order\$1) same	US-PGPUB;	14:51
		concentration	EPO; JPO;	1,
		Concentration	DERWENT	
	,	5550070 mm	USPAT;	2002/12/06
-	2	5550070.pn.		17:32
			US-PGPUB;	17:32
			EPO; JPO;	
			DERWENT	0000/05/05
-	370	(interlayer with insulat\$3 with silicon	USPAT;	2003/06/06
		with nitride) and (interlayer with	US-PGPUB;	12:32
		insulat\$3 with (acrylic or polyimide or	EPO; JPO;	
		polyamide or epoxy or epoxies)) and gate	DERWENT	
-	37	((interlayer with insulat\$3 with silicon	USPAT;	2003/06/06
		with nitride) and (interlayer with	US-PGPUB;	12:33
		insulat\$3 with (acrylic or polyimide or	EPO; JPO;	
		polyamide or epoxy or epoxies)) and gate)	DERWENT	
	1	and @ad<19970610		
<u>-</u>	2		USPAT;	2003/09/30
	"	00000 / 0 · pii.	US-PGPUB;	20:08
			EPO; JPO;	
	1		DERWENT	
	2050		1	2002/12/09
-	2258	silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	18:16
		amorphous)	EPO; JPO;	
			DERWENT	/ /
-	968	(silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	18:42
	1	amorphous)) and @ad<19970610	EPO; JPO;	
	1		DERWENT] .
-	67	(silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	15:28
		amorphous)) same source same drain same	EPO; JPO;	
		gate	DERWENT	
I _	17		USPAT;	2003/12/08
	''	(crystallization or crystaliz\$3 or	US-PGPUB;	16:14
				1 20.13
		amorphous)) same source same drain same	EPO; JPO;	
	_	gate) and @ad<19970610	DERWENT	2002/12/00
-	6		USPAT	2003/12/08
	_	"5330935" "5403772" "5426064").PN.		15:38
-	54	5550070.URPN.	USPAT	2003/12/08
1			1	16:13

-	1	((silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	16:16
		amorphous)) same source same drain same	EPO; JPO;	
		gate) and (concentration with nickel with	DERWENT	
	6	(source or drain) with channel) ((silicon with (nickel or ni) with	TICDATE.	2003/12/08
-	6		USPAT; US-PGPUB;	16:32
		(crystallization or crystaliz\$3 or amorphous)) same source same drain same	EPO; JPO;	10.32
		gate) and (concentration same nickel same	DERWENT	
		(source or drain) same channel)	DEKMENI	
_	1	((silicon with (nickel or ni) with	USPAT;	2003/12/08
-	.	(crystallization or crystaliz\$3 or	US-PGPUB;	18:17
		amorphous)) same source same drain same	EPO; JPO;	10.17
		gate) and (concentration same (iron or	DERWENT	
1		palladium or copper) same (source or	<i>D D D D D D D D D D</i>	
		drain) same channel)		
_	1	((silicon with (nickel or ni) with	USPAT;	2003/12/08
	1	(crystallization or crystaliz\$3 or	US-PGPUB;	16:33
		amorphous)) same source same drain same	EPO; JPO;	13,00
		gate) and (concentration same iron same	DERWENT	
1		(source or drain) same channel)		
_	6	(silicon with (nickel or ni) with	USPAT;	2003/12/08
	l	(crystallization or crystaliz\$3 or	US-PGPUB;	17:00
1		amorphous)) and (concentration same	EPO; JPO;	
	l	(iron or palladium or copper) same	DERWENT	
		(source or drain) same channel)		
_	171	(silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	17:00
		amorphous)) and (phosphorus with	EPO; JPO;	
	1	getter\$3 with nickel)	DERWENT	
- /	2	((silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	17:05
		amorphous)) and (phosphorus with	EPO; JPO;	
		getter\$3 with nickel)) and @ad<19970610	DERWENT	
_	19	((silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	17:11
		amorphous)) and (phosphorus with	EPO; JPO;	
		getter\$3 with nickel)) and @ad<19980610	DERWENT	
-	96	(silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	17:12
		amorphous)) and (nickel with source with	EPO; JPO;	
	_	drain with channel)	DERWENT	2002/12/00
1 -	24	((silicon with (nickel or ni) with	USPAT;	2003/12/08
		(crystallization or crystaliz\$3 or	US-PGPUB;	17:12
		amorphous)) and (nickel with source with	EPO; JPO;	
		drain with channel)) and @ad<19970610	DERWENT USPAT	2002/12/09
-	14	("5147826" "5275851" "5481121"	USPAI	2003/12/08 17:21
	1	"5492843" "5501989" "5529937" "5534716" "5543352" "5550070"		1 - 1 - 2 - 2
1	1	"5534716" "5543352" "5550070" "5580792" "5585291" "5612250"		
		"5643826" "5654203").PN.		
1_	1370	silicon with iron with (crystallization	USPAT;	2003/12/08
-] 13/0	or crystaliz\$3 or amorphous)	US-PGPUB;	18:16
i		or orasearrage or amorphoda,	EPO; JPO;	
			DERWENT	
1_	3	(silicon with iron with (crystallization	USPAT;	2003/12/08
		or crystaliz\$3 or amorphous)) and	US-PGPUB;	18:41
	1	(concentration same (iron or palladium or	EPO; JPO;	
		copper) same (source or drain) same	DERWENT	
		channel)		
-	6	· · · · · · · · · · · · · · · · · · ·	USPAT;	2003/12/08
		palladium or copper) with source with	US-PGPUB;	18:42
		drain with channel) and @ad<19970610	EPO; JPO;	
		,	DERWENT	
-	30	concentration with (nickel or iron or	USPAT;	2003/12/08
		palladium or copper) with source with	US-PGPUB;	20:13
1		drain with channel	EPO; JPO;	
			DERWENT	1

_	-	19	, , , , , , , , , , , , , , , , , , , ,	USPAT	2003/12/08
			"5616506" "5639698" "5643826"		18:48
			"5700333" "5736438" "5773309"	,	
			"5773329" "5821138" "5834071"		
			"5834345" "5869363" "5879977"		
			"5897347" "5923962" "5956579"		
			"6087245").PN.		[
-		0	concentration with nickel with source	USPAT;	2003/12/08
			with drain with channel with magnitude	US-PGPUB;	20:16
				EPO; JPO;	
1				DERWENT	
-		29	concentration with nickel with source	USPAT;	2003/12/08
			with drain with channel	US-PGPUB;	20:14
				EPO; JPO;	
				DERWENT	
_		0	nickel with source with drain with	USPAT;	2003/12/08
		,	channel with magnitude	US-PGPUB;	20:17
			,	EPO; JPO;	
				DERWENT	
_		4	nickel with source with drain with	USPAT;	2003/12/08
		•	channel with (double or times)	US-PGPUB;	20:17
1			(404420 02 024020)	EPO; JPO;	
1				DERWENT	
1_		2	nickel with source with drain with	USPAT;	2003/12/08
		_	channel with higher	US-PGPUB;	20:18
			onamici with might	EPO; JPO;	
				DERWENT	
_		6	nickel with source with drain with	USPAT;	2003/12/08
			channel with lower	US-PGPUB;	20:25
				EPO; JPO;	
				DERWENT	
1_		165	nickel with channel with concentration	USPAT;	2003/12/08
		105	interest with ondinier with our outlier	US-PGPUB;	20:25
1				EPO; JPO;	
				DERWENT	
_		34	(nickel with channel with concentration)	USPAT;	2003/12/08
		34	and @ad<19970610	US-PGPUB;	20:26
			and Gad(1)9/0010	EPO; JPO;	23.20
				DERWENT	
1.		9019939	((nickel with channel with concentration)	USPAT;	2003/12/08
-		9019339	and @ad<19970610) no (energy adj	US-PGPUB;	20:26
1			laboratory)	EPO; JPO;	23.20
			TanotacotA)	DERWENT	
1		I	l .	LDEKMENI	